

	L #	Hits	Search Text
1	L1	47493	(mask or reticle) and (wafer and substrate)
2	L2	0	(mask or reticle) with ((duty near ratio) and (through-pitch) and (through near pitch))
3	L4	0	(mask or reticle) with (through-pitch)
4	L3	84	(mask or reticle) with (duty near ratio)
5	L5	64	1 and 3
6	L6	58	5 and (355/\$.ccls. or 430/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
7	L7	47493	(mask or reticle) and (wafer and substrate)
8	L8	64	3 and 7
9	L9	58	8 and (355/\$.ccls. or 430/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
10	L10	33	(mask or reticle) with ((dense adj pattern) and (isolated adj pattern))
11	L11	0	(mask or reticle) with ((critical adj dimension) and ("depth of focus"))
12	L12	930	(mask or reticle) with (critical adj dimension)

	L #	Hits	Search Text
13	L13	0	(mask or reticle) with "depth of focus"
14	L14	812	(mask or reticle) with (focus near2 depth)
15	L15	52	12 and 14
16	L16	40	15 and (355/\$.ccls. or 430/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
17	L17	3	787364.ap.
18	L18	1	("5838426").PN.
19	L19	28	10 and (355/\$.ccls. or 430/\$.ccls. or 250/\$.ccls. or 356/399-401.ccls.)
20	L20	0	19 not 10
21	L21	5	10 not 19
22	L22	5	(multiple near expos\$5) and 19

P/K
Sept 8, 03